

THE DECOMPOSITION OF SOME TERTIARY ACYL HYPOCHLORITES

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In recent years the photochemical and thermal decomposition of tertiary hypochlorites have received much attention and their free radical chain mechanism elucidated^{2,3}. These compounds undergo decomposition to carbonyl compounds and alkyl chlorides. The structure of the products appears to depend upon the nature of the R groups and their subsequent stability as a free radical which is generated in the β -scission process.



We have set out to study a series of tertiary α -acyl hypochlorites in hopes of finding a new method for generating the acyl radical and establishing its order of stability with various alkyl radicals.

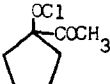
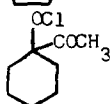
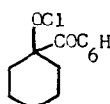


We, at this time, would like to report our preliminary findings on five of these.

Each hypochlorite was prepared by treatment of the corresponding tertiary ketols with hypochlorous acid in carbon tetrachloride³. The solutions were then assayed iodometrically and refluxed in the dark from 5 to 30 minutes at which time all the hypochlorite had decomposed.

TABLE 1

Decomposition of Tertiary Acyl Hypochlorites in Refluxing CCl_4

Hypochlorite	Products ^a	Yield %
(1) $\text{CH}_3\text{CH}_2\overset{\text{CH}_3}{\underset{\text{OCl}}{\text{C}}}-\text{COCH}_3$	2-butanone; acetyl chloride	99 ^b
(2) $(\text{CH}_3)_2\text{COCOC}_6\text{H}_5$	benzoyl chloride; acetone	95 ^c
(3) 	cyclopentanone; acetyl chloride $\text{ClCH}_2(\text{CH}_2)_3\text{COCOC}_6\text{H}_5$	90 < 6 ^d
(4) 	cyclohexanone; acetyl chloride 2-chlorocyclohexanone	46 ^e 44 ^e
(5) 	cyclohexanone; benzoyl chloride 2-chlorocyclohexanone $\text{ClCH}_2(\text{CH}_2)_4\text{COCOC}_6\text{H}_5$	42 ^e 43 ^e < 5 ^d

^aIdentity of all products established by retention times in the gas chromatograph and by infrared analysis.

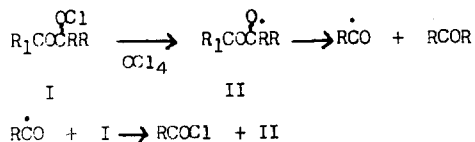
^bNo other products indicated by gas chromatography.

^cIdentified as benzoic acid after hydrolysis.

^dUnidentified high boiling peak.

^eYield established by gas chromatography using the internal standard method⁴.

The proposed mechanism for this reaction is analogous to that suggested by Walling and Greene in their studies of the fragmentation of tertiary hypochlorites^{2,3}.





It is of interest to compare the products of compounds (3), (4) and (5) in Table I with Greene's results with the hypochlorites of isopropyl cyclohexanol and isopropyl cyclopentanone³. Although we have not been able to identify any ring opening products

it is fair to say our system seems more favorably disposed toward acyl cleavage rather

TABLE 2³

Products of Decomposition of Tertiary Hypochlorites

<u>Hypochlorite</u>	<u>Solvent</u>	<u>Products</u>	<u>Yield %</u>
	CCl ₄ ^a	isopropyl chloride; cyclohexanone (CH ₃) ₂ CHCO(CH ₂) ₄ CH ₂ Cl 2-chlorocyclohexanone	66 13.5 <0.5 ^b
	CFCl ₃ ^c	(CH ₃) ₂ CHCO(CH ₂) ₃ CH ₂ Cl isopropyl chloride; cyclopentanone	94 3.4

^aThermal initiation at 80°.

^bNot present within the limits of detection of the analysis.

^cWeak ultraviolet initiation at 0°.

than alkyl cleavage and the amount of 2-chlorinated cyclic ketone in our case is much higher. This selectivity in the mode of cleavage indicates a new and potentially useful method of generating acyl radicals.

Acyl radicals have been shown to be intermediates in vapor phase decompositions of some ketones and aldehydes and are usually generated in solution by peroxides or photochemically⁵. They have also been shown to be intermediates in the cobaltic salt oxidations of aldehydes⁶. The photolysis of xanthates⁷ and the reaction of tri-alkyltin hydrides with acid chlorides⁸ represent other and more recently reported methods of producing the acyl radical.

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